



Canadian Association
of Physicists

Association canadienne
des physiciens et physiciennes

Contribution ID: 3450

Type: **Invited Speaker / Conférencier(ère) invité(e)**

(I) Plasma Immersion Ion Implantation: Physics & Applications

Wednesday, 8 June 2022 13:15 (30 minutes)

Many materials science applications require high fluence ion implantation. Plasma Immersion Ion Implantation (PIII) is a technique in which the target to be implanted is immersed in the plasma, and implanted using negative-polarity high-voltage pulses. PIII has many applications including advanced semiconductor processing [1], photonic devices [2-3], ion implantation of advanced materials such as graphene [4], corrosion inhibition of metals [5], and most recently, studies of ion bombardment of plasma-facing components for plasma fusion applications. PIII has the advantage that very high ion fluences can be implanted over large area targets, without the beam scanning and complicated target mounts required for conventional beamline ion implantation. The PIII process involves complex physics which requires detailed study as the technology is further developed as a materials processing tool. This talk will discuss the PIII method in detail and highlight some important aspects of the underlying physics. which are being further developed in the Bradley Lab at the University of Saskatchewan.

References

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Session Classification: W2-7 Plasma-Matter interactions (DPP) | Interactions plasma-matière (DPP)

Track Classification: Technical Sessions / Sessions techniques: Plasma Physics / Physique des plasmas (DPP)